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(12) **United States Design Patent** (10) **Patent No.:** **US D868,124 S**
Riker et al. (45) **Date of Patent:** **** Nov. 26, 2019**

(54) **TARGET PROFILE FOR A PHYSICAL
VAPOR DEPOSITION CHAMBER TARGET**

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(**) Term: **15 Years**

Sputtering Targets, posted at Angstrom Sciences, posting date May 5, 2016. Site visited Apr. 1, 2019. URL: <<https://web.archive.org/web/20160505015447/https://www.angstromsciences.com/sputtering-targets>> (Year: 2016).*

(Continued)

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(52) **U.S. Cl.**

USPC **D15/144**; D15/150; D15/199; D13/182

(58) **Field of Classification Search**

USPC D22/113, 199; D13/182; D15/144.1,

D15/144.2, 144, 150, 199

CPC H01L 21/67742; H01L 21/0226; H01L

21/02263; H01L 21/02266; H01L

21/02269; H01L 21/02271; H01L

2224/75186; H01L 2224/761185; H01L

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21/02631; C23C 14/3407; C23C 14/35;

C23C 8/00; C23C 10/00; H01J 37/3414;

H01J 37/3423

See application file for complete search history.

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(57)

CLAIM

The ornamental design for a target profile for a physical vapor deposition chamber target, as shown and described.

DESCRIPTION

FIG. 1 is a top perspective view of a target profile for a physical vapor deposition chamber target.

FIG. 2 is a top plan view thereof.

FIG. 3 is a bottom plan view thereof.

FIG. 4 is a right side plan view thereof.

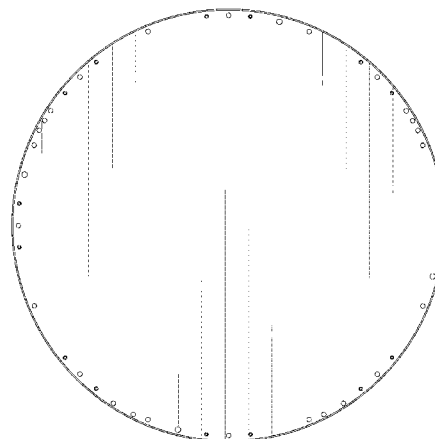
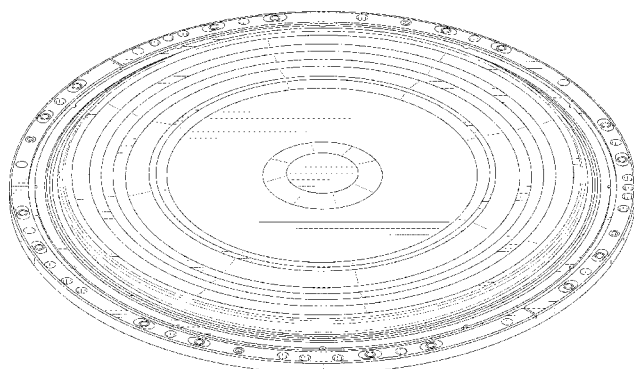
FIG. 5 is a left side plan view thereof.

FIG. 6 is a front view thereof.

FIG. 7 is a back view thereof; and,

FIG. 8 is an enlarged cross sectional view taken along line 8-8 in FIG. 2.

1 Claim, 6 Drawing Sheets



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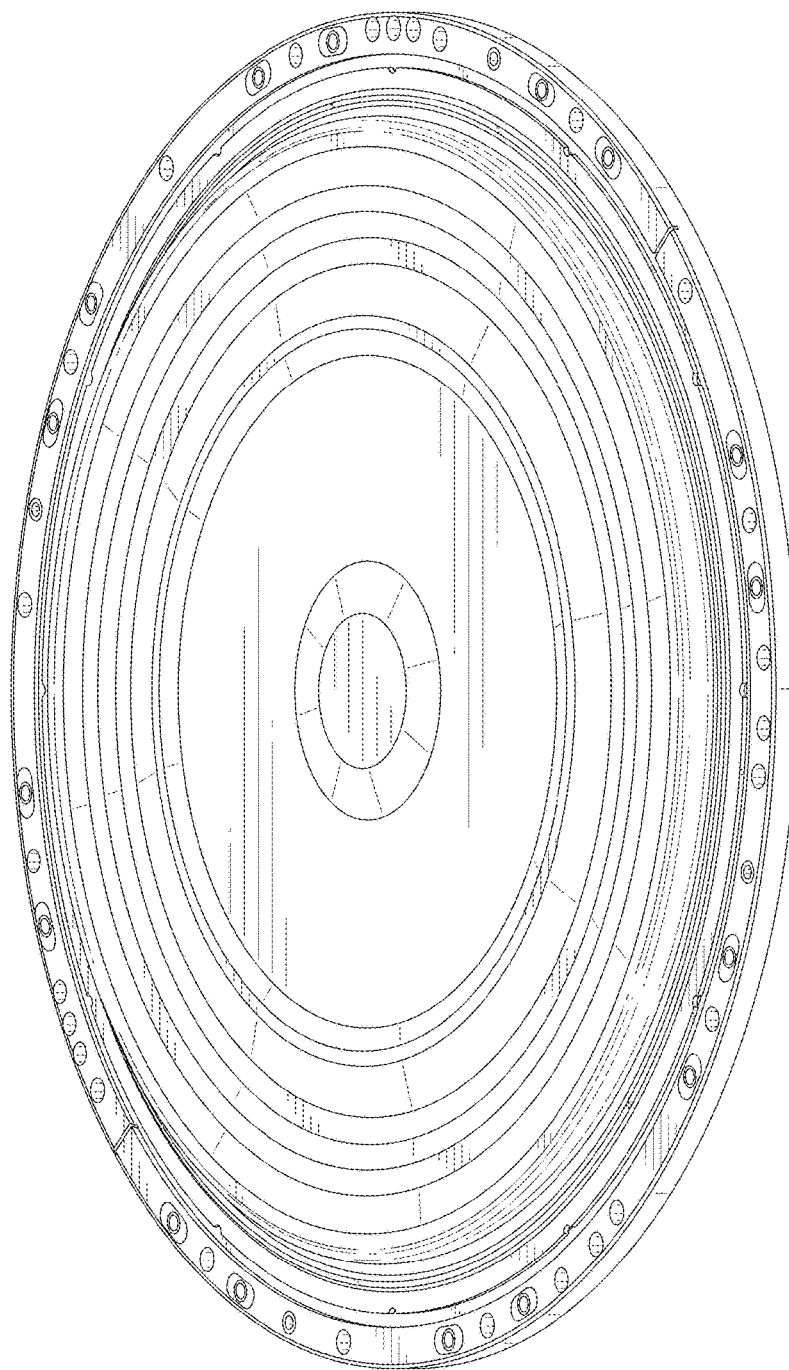


FIG. 1

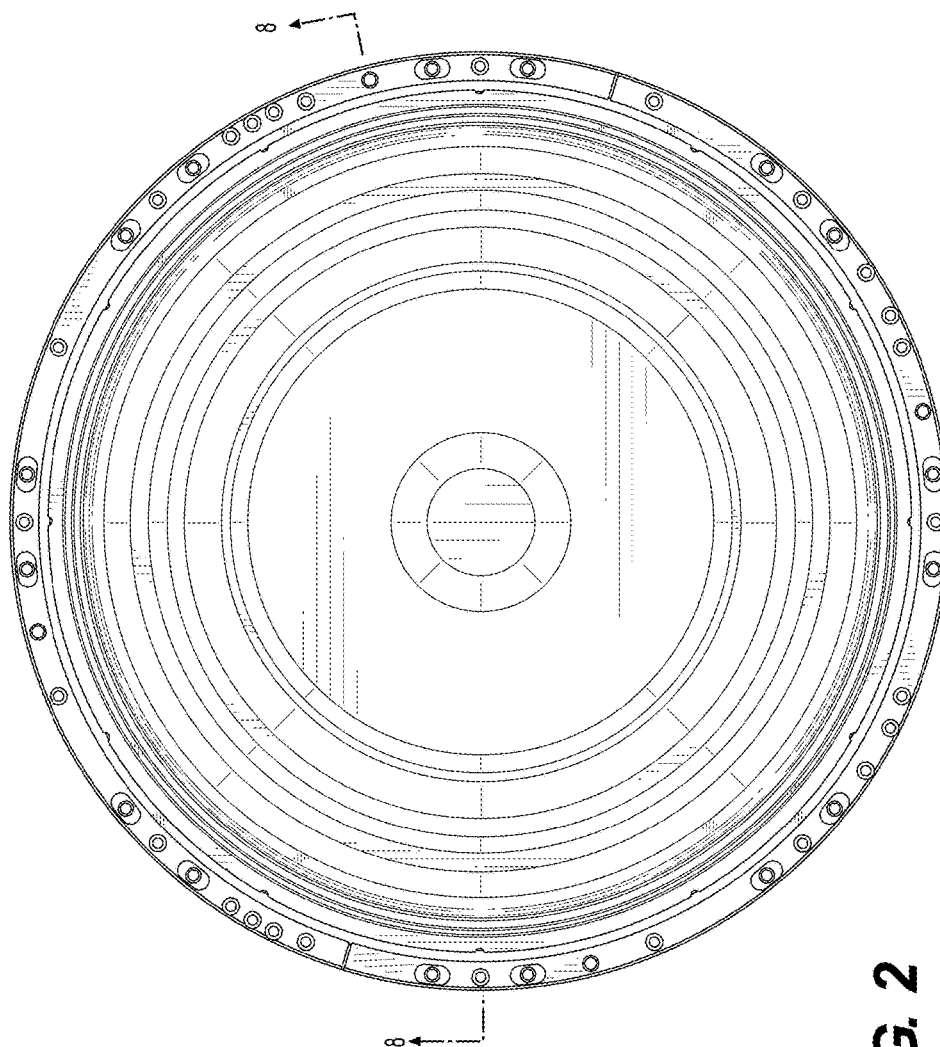


FIG. 2

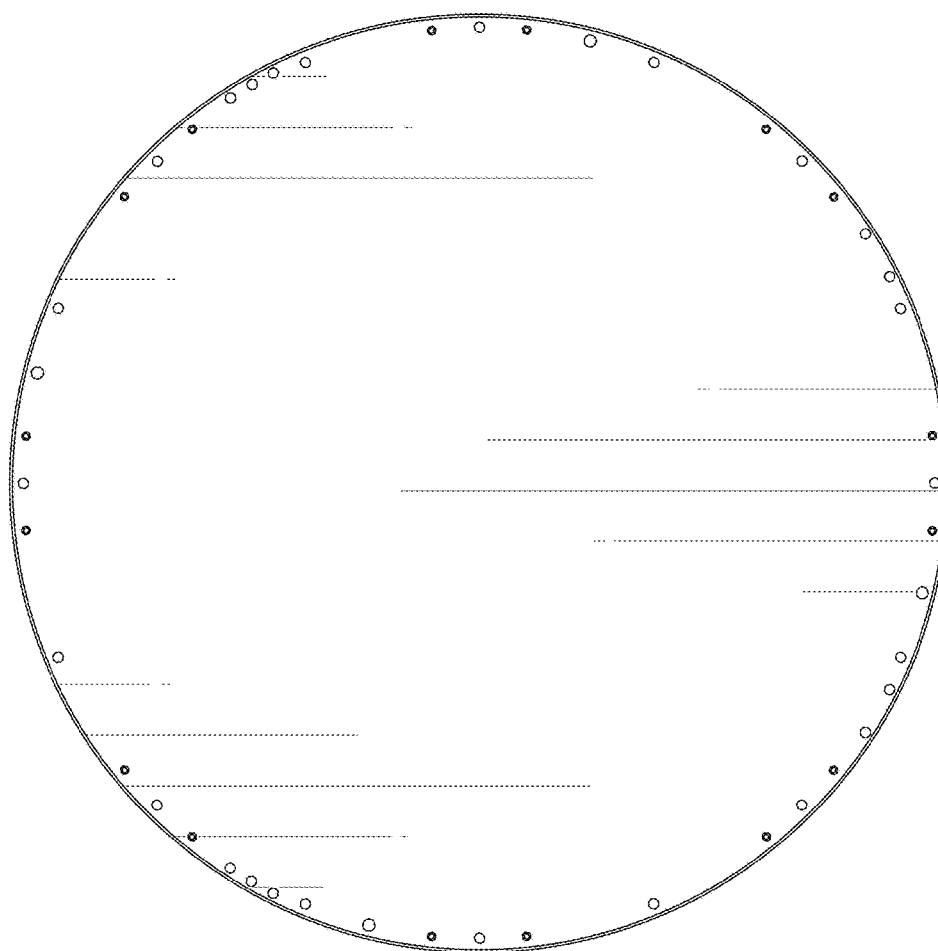


FIG. 3

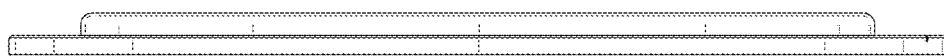


FIG. 4

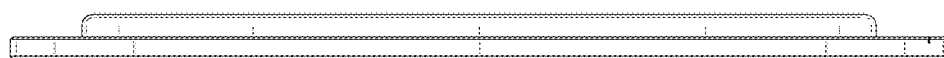


FIG. 5

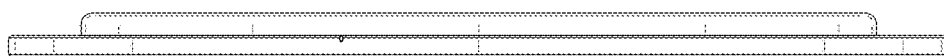


FIG. 6

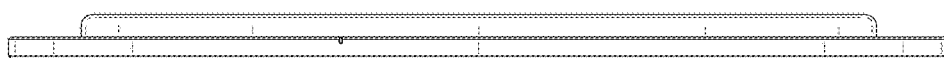


FIG. 7



FIG. 8